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WONIK MATERIALS

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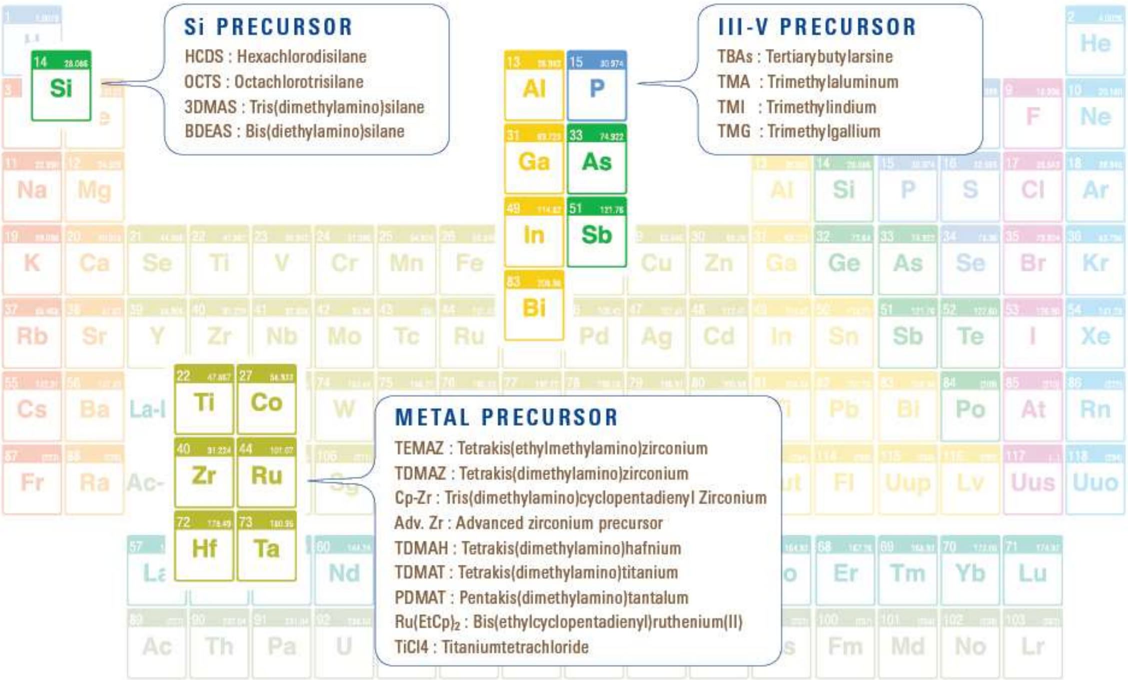
Precursors

PRECURSOR



Si PRECURSOR

HCDS : Hexachlorodisilane
OCTS : Octachlorotrisilane
3DMAS : Tris(dimethylamino)silane
BDEAS : Bis(diethylamino)silane

III-V PRECURSOR

TBAs : Tertiarybutylarsine
TMA : Trimethylaluminum
TMI : Trimethylindium
TMG : Trimethylgallium

METAL PRECURSOR

TEMAZ : Tetrakis(ethylmethylamino)zirconium
TDMAZ : Tetrakis(dimethylamino)zirconium
Cp-Zr : Tris(dimethylamino)cyclopentadienyl Zirconium
Adv. Zr : Advanced zirconium precursor
TDMAH : Tetrakis(dimethylamino)hafnium
TDMAT : Tetrakis(dimethylamino)titanium
PDMAT : Pentakis(dimethylamino)tantalum
Ru(EtCp)$_2$: Bis(ethylcyclopentadienyl)ruthenium(II)
TiCl4 : Titaniumtetrachloride

R&D CENTER

Gas & Precursor Development
(New applications/ Materials)
Customized purification Lab.
(UHP Grade, Mixed materials)
Deposition R&D Lab.
Surface Analysis Lab.
Pilot Plant

Yangcheong Plant

PRECURSOR PLANT

Explosion-proof structure
Synthesis & UHP Purification
Auto canister handling system
Materials Analysis Lab.

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Precursor is one of our new business portfolio. Currently completed Precursor plant and R&D Center set up in Yangcheong. These new high-tech facilities can strengthen our safety level and meet customers’ needs on new materials.

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PRODUCT LINE UP

Stock Sales

Product	Purity	Package		Manufacture type	Key para. (Impurity)
		Cylinder (L)	Valve type		
Si2H6	4N8	49	DISS 632	Stock	SiH4, N2, H2O
GeH4 Mix (10%)	4N8	47	DISS 632	Stock	Concentration
C2H4	5N	47	DISS 724	Stock	H2O, N2, OHC
CF4	5N	47, 440	JIS 22R, DISS 716	Stock	H2O, N2, OFC
CH2F2	4N	47	JIS 22L	Stock	H2O, N2, OFC

Precursors

Product	Purity	Package		Manufacture type	Key para. (Impurity)
		Cylinder (L)	Valve type		
HCDS	6N	19L, 38L	Customized	Synthesis, Distillation	Assay, Metal
BDEAS	6N	19L	Customized	Distillation	Assay, Metal, Cl-
TiCl4	7N	19L	Customized	Distillation	Assay, Metal, Moisture

THANK YOU